

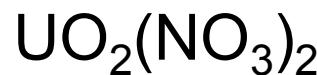
Low Temperature Synthesis and Sintering of UO_2 Nanoparticles

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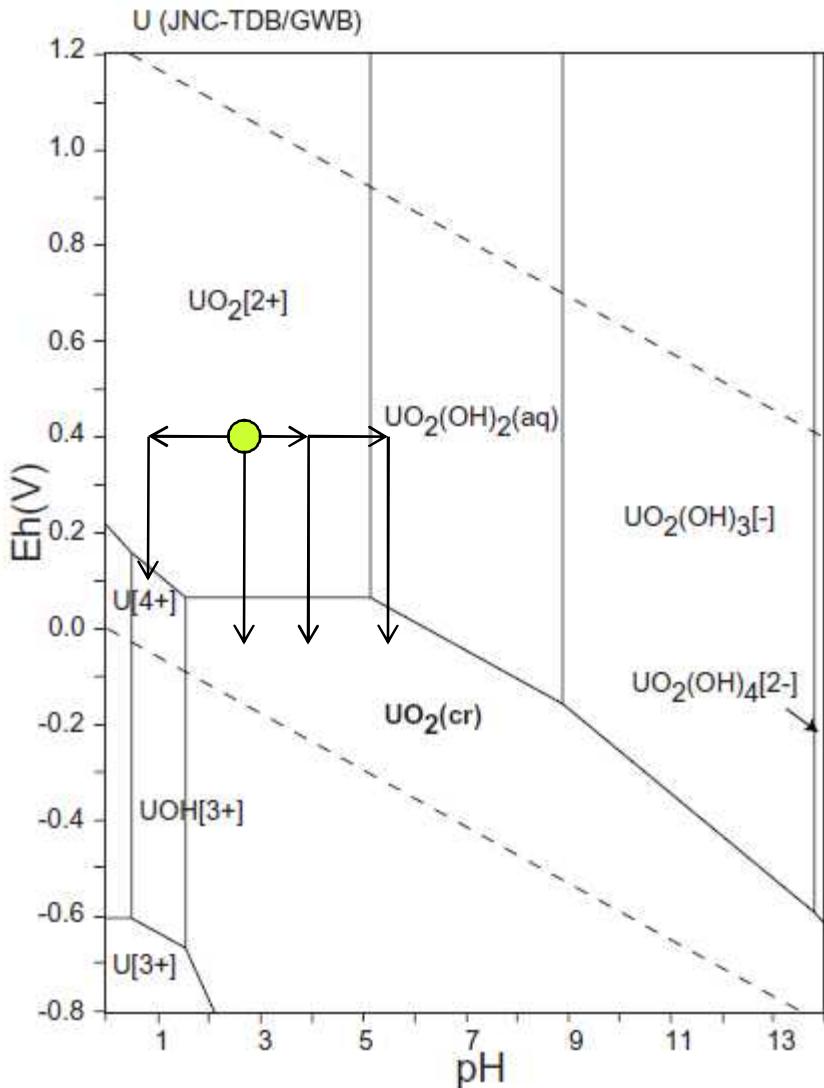
UO₂ processing



Goals

- Understand how UO_2^{2+} becomes UO_2
- Develop more efficient processing with fewer high-temperature steps
- Minimize volatilization of actinides

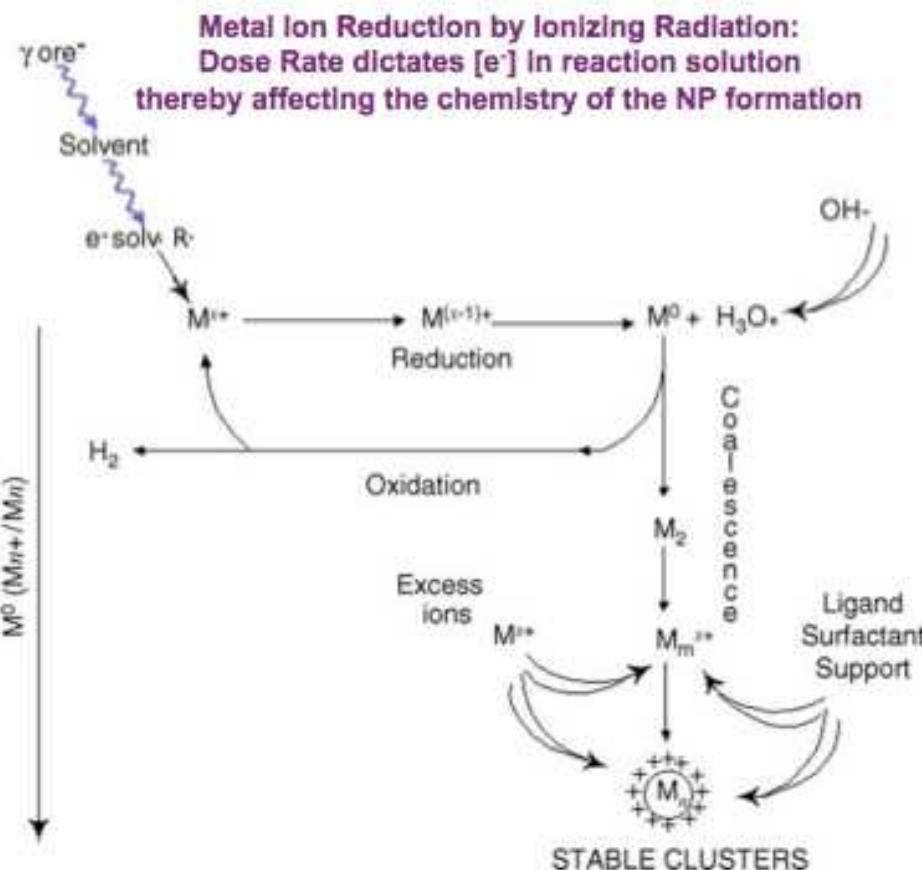
U Pourbaix diagram



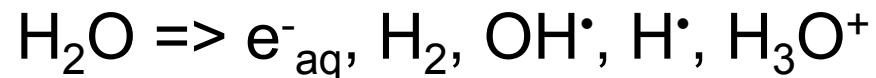
We use pH adjustment and gamma irradiation to find a convenient, high-yield path to UO_2

Then use heated-stage TEM to observe initial stages of sintering

Radiochemistry of Nanoparticles



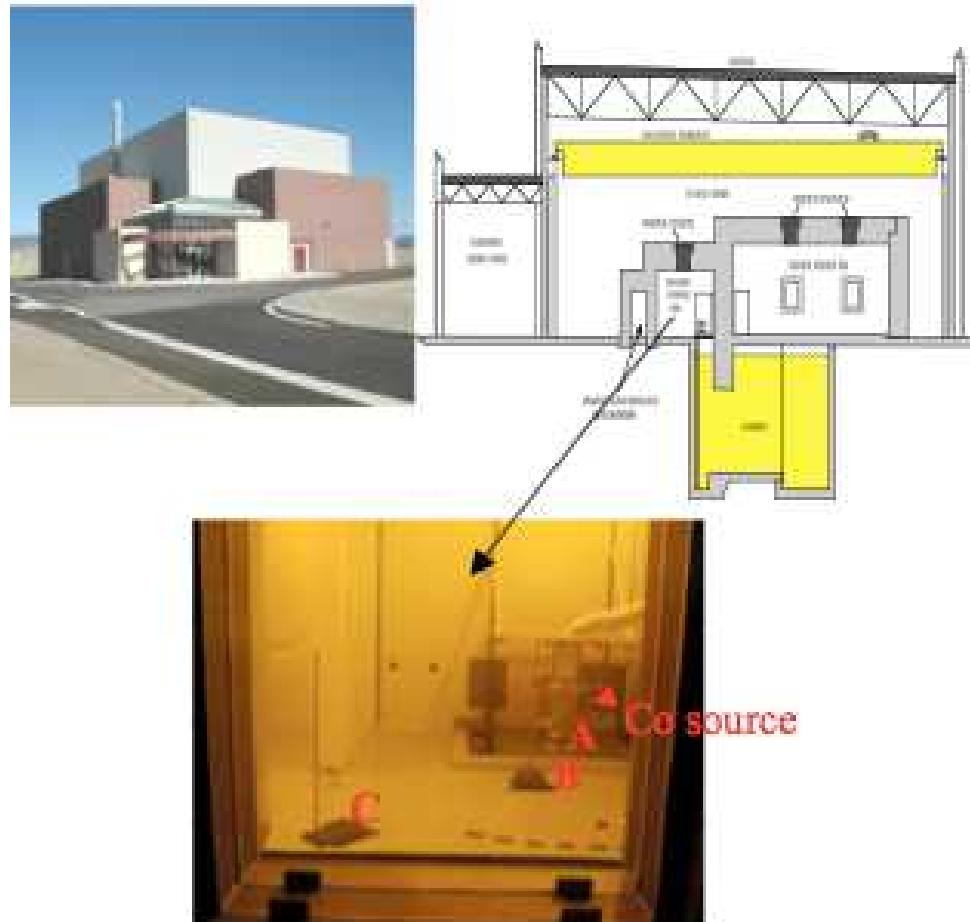
Gamma produces strong oxidizers and reductants (nonequilibrium)





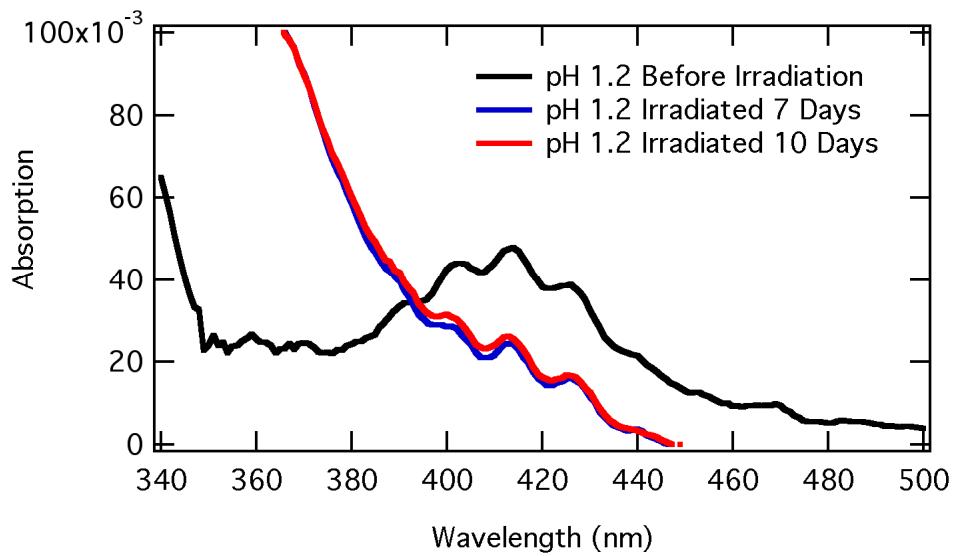
Sandia's Gamma Irradiation Facility

GIF: ^{60}Co source : $1.345 \times 10^5 \text{ Ci}$



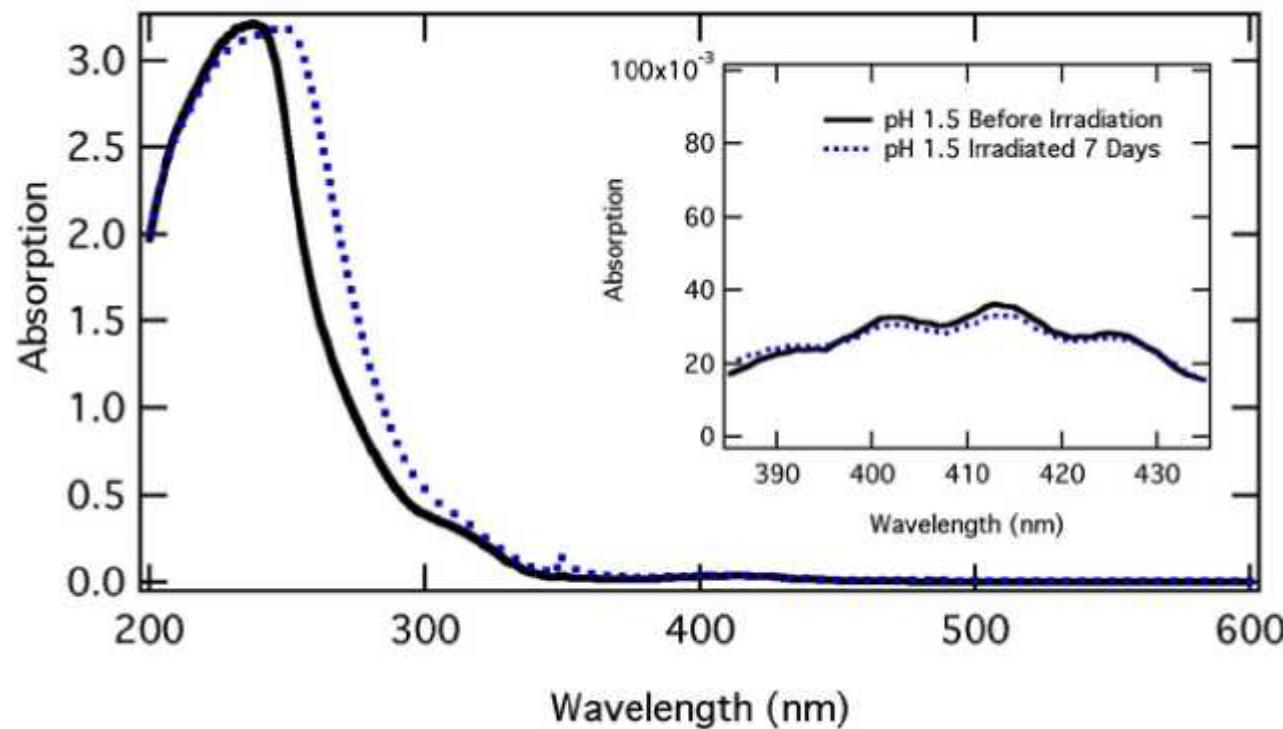


Strongly acidic conditions



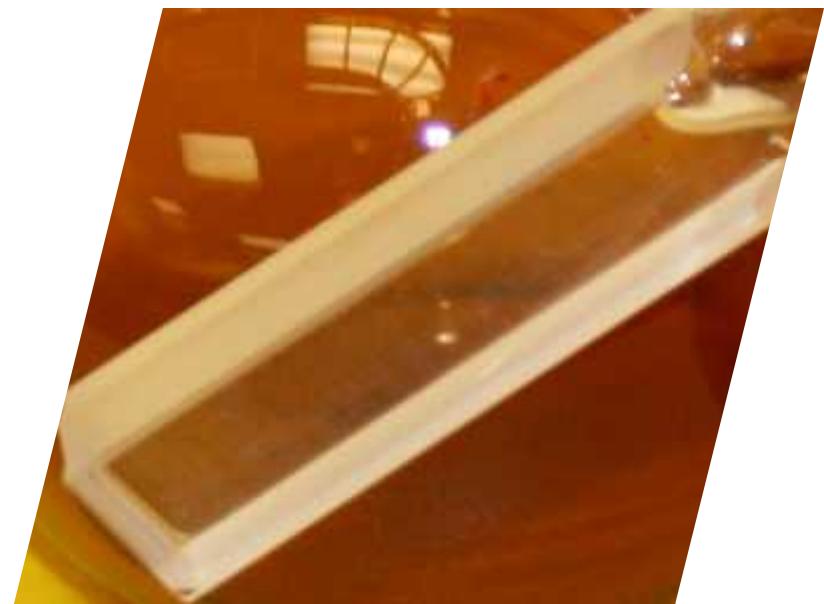
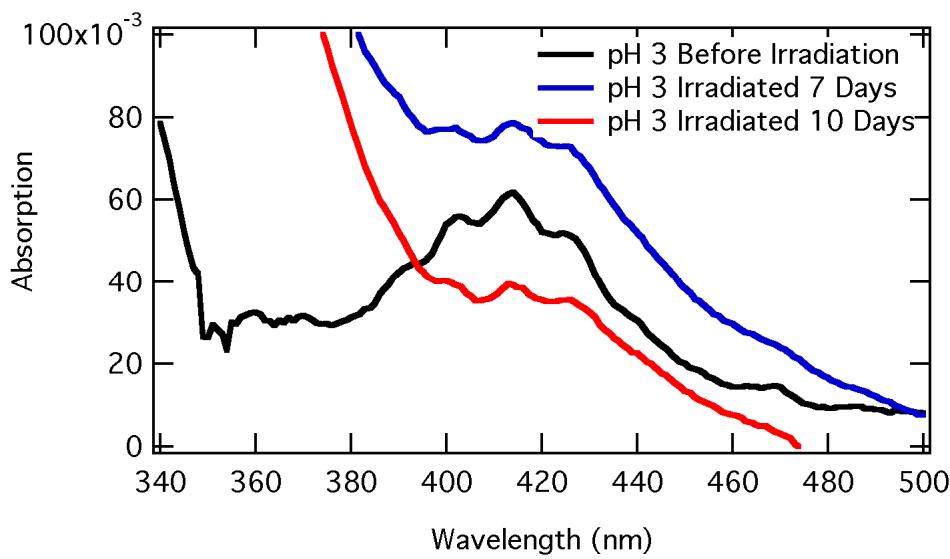
Incomplete reaction

Chloride vs. nitrate



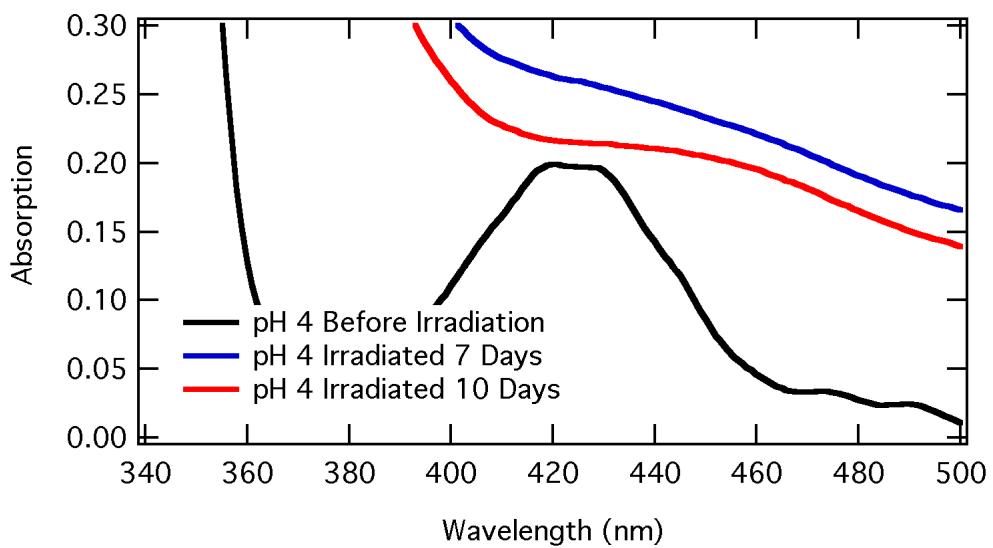
Chloride interacts differently with reactants

Acidic conditions



Cloudier product

Weakly acidic



Precipitate forms
Different reactant species are
present





Protochips heated TEM stage

Old approach: resistive heating of entire stage

- Requires cooling water, which frequently clogs
- Severe drift
- Noise/oscillation problems
- Slow ramp rates and settling

Protochips:

- Heat only a microfabricated grid
- Ramps 1000 C / ms, RT – 1200 C
- Also permits electrical measurement





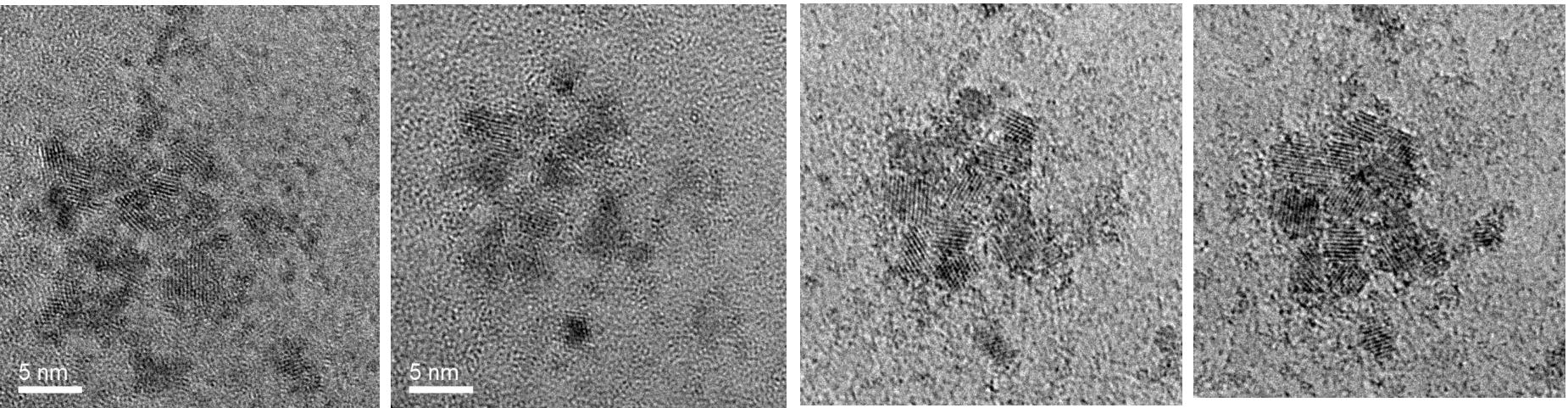
pH 3 heating

RT

200 °C

400 °C

500 °C

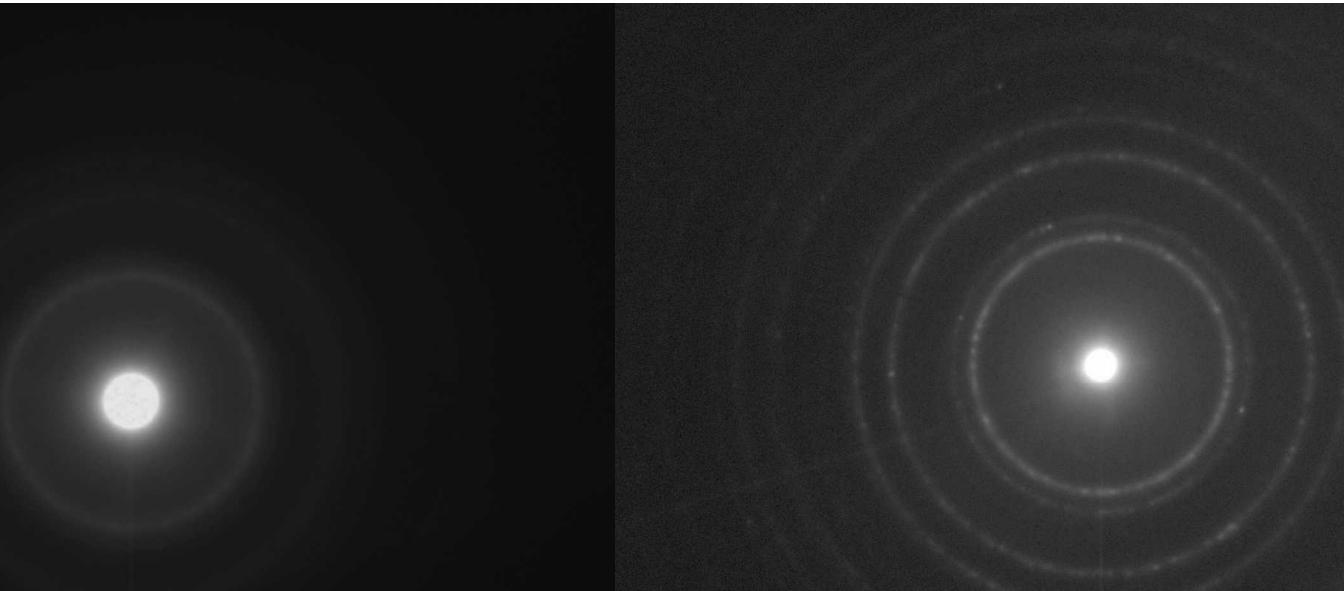


Consolidation is observed on TEM grid



Electron diffraction patterns (pH 3)

Sharper lines indicate grain growth



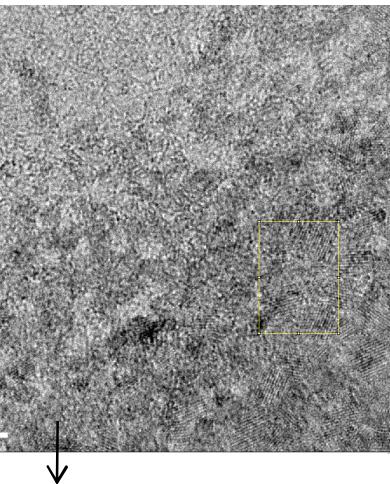
RT

500 °C

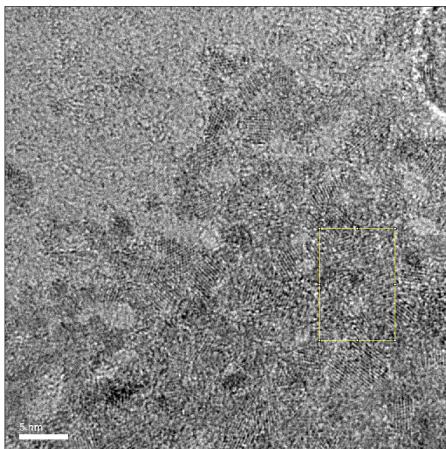


pH 1.5 heating (with chloride)

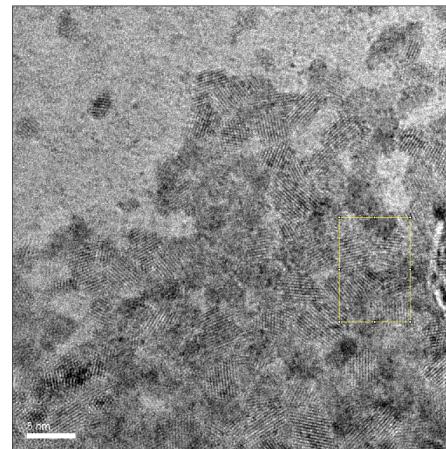
RT



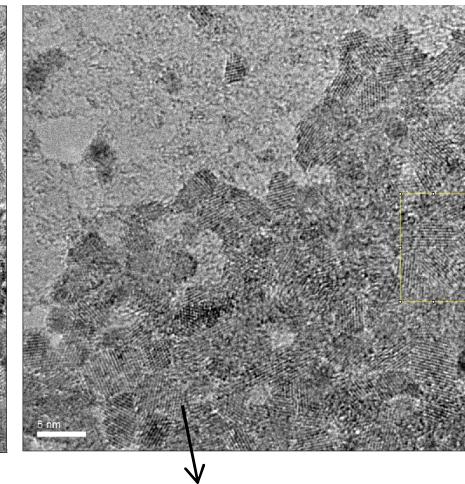
300 °C



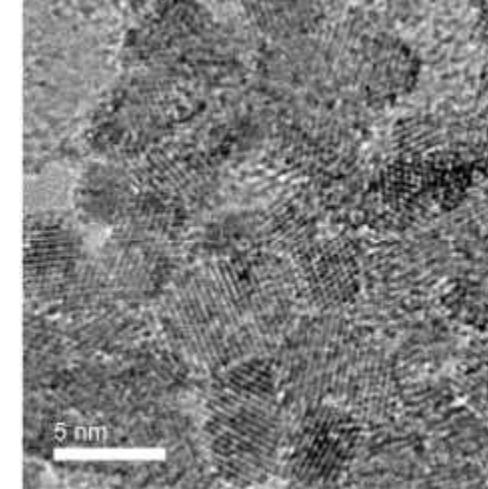
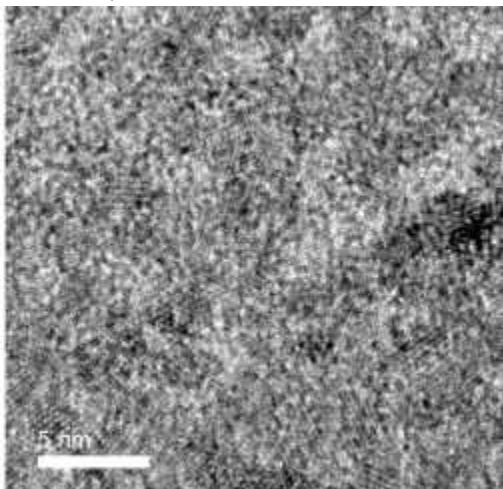
500 °C



600 °C



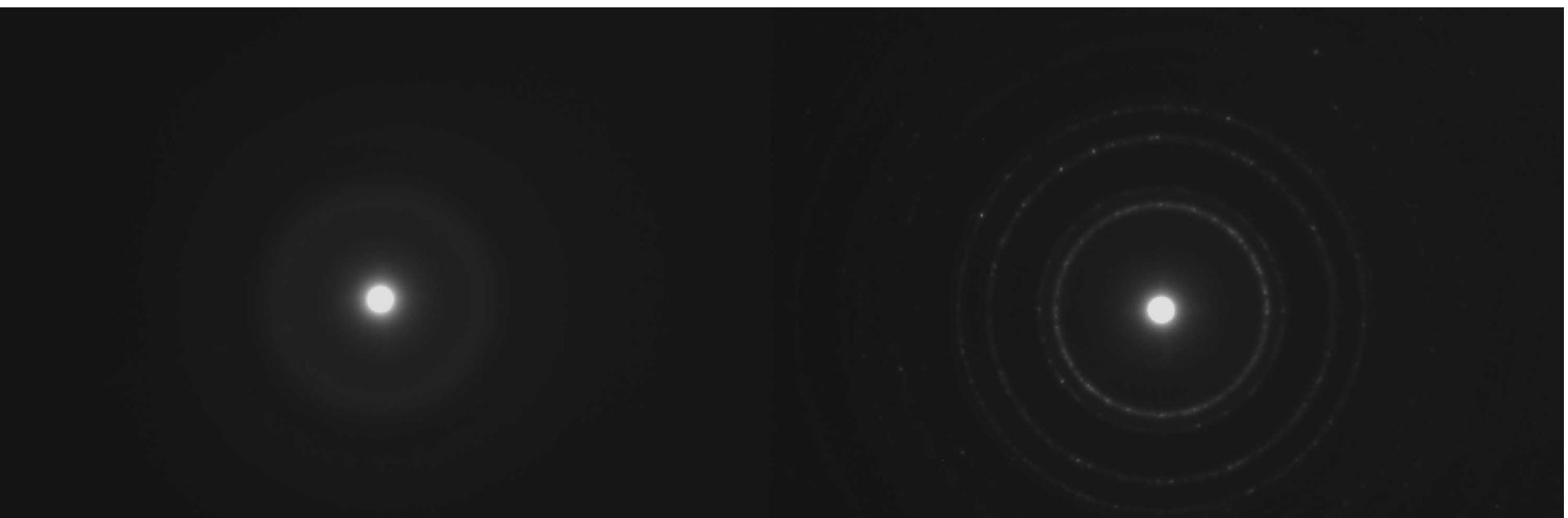
Likely a mixture of UO_2 and dried reactant
- still consolidates





Electron diffraction (pH 1.5, chloride)

Grain growth is also observed, but less
crystalline starting (and ending) point

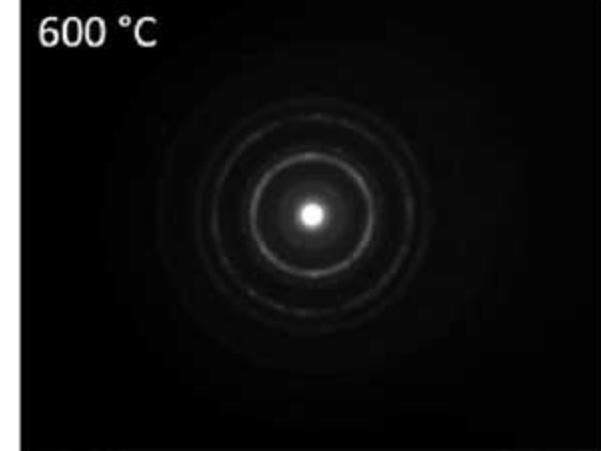
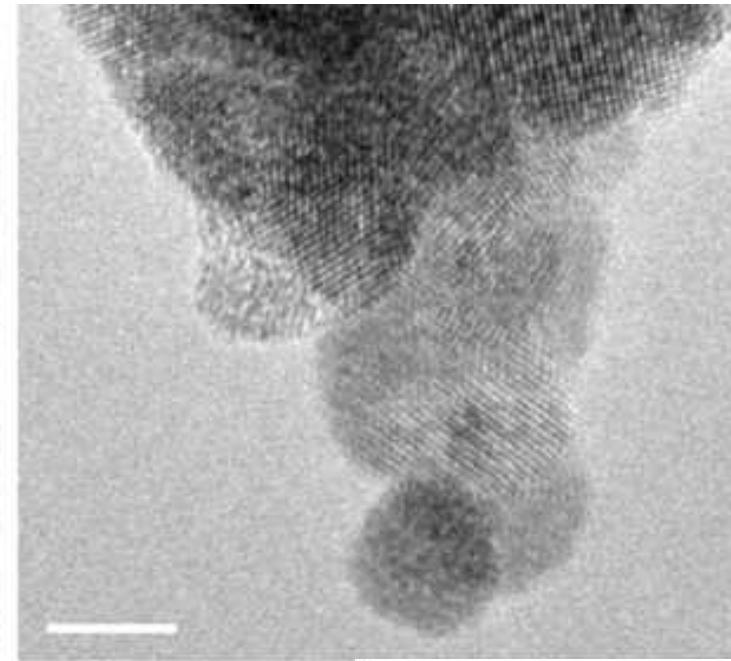
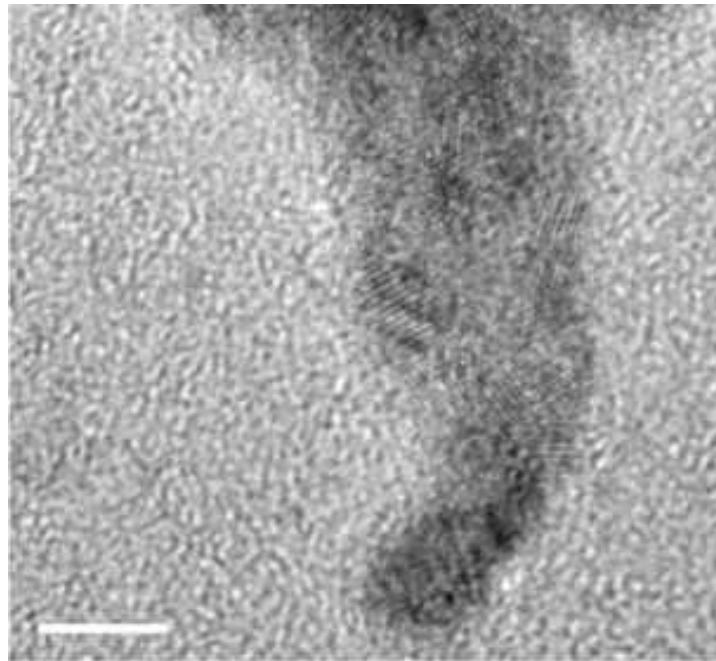


RT

600 °C



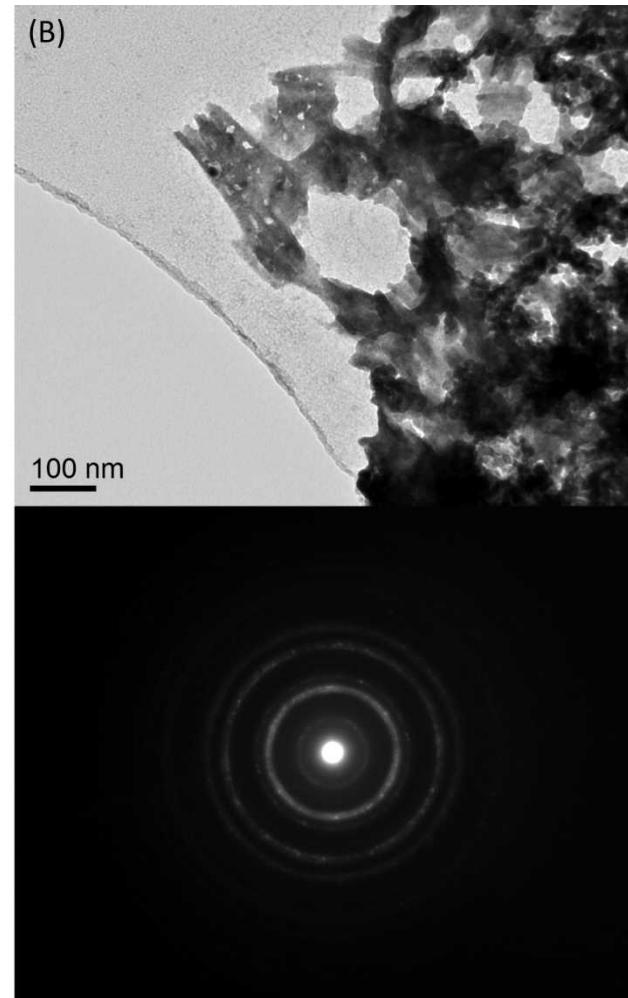
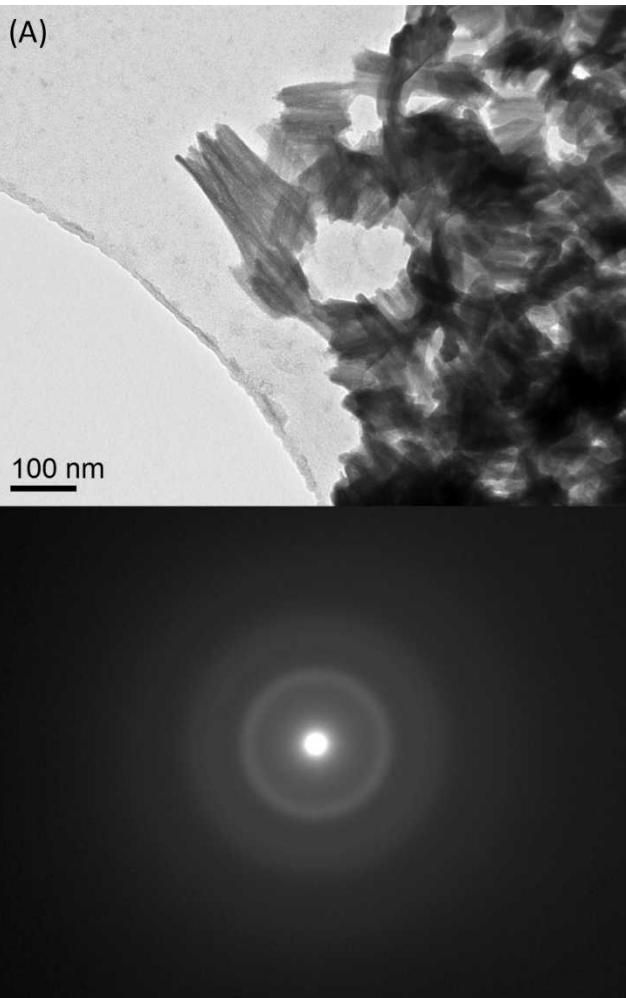
pH 4



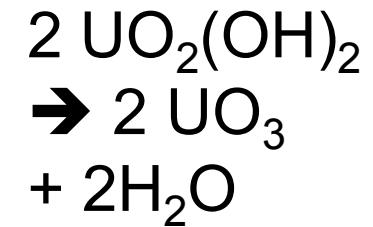
Clear grain growth



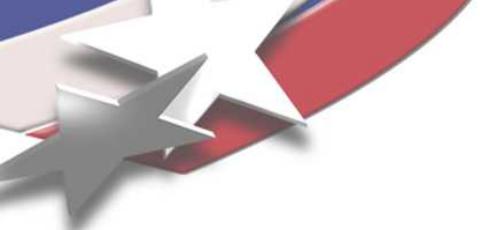
pH 4: Condensation



Holes form



Partial reactant precipitation at higher pH



pH 4 sintering movie

11-05-2010

U oxide

200 to 800 C

SF 4-9-8



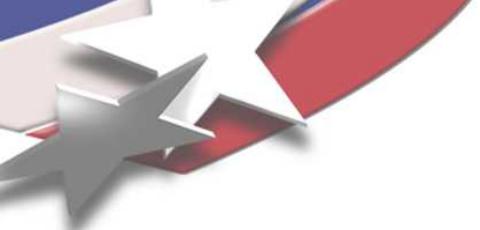
pH 4 condensation movie

11-05-2010

U oxide

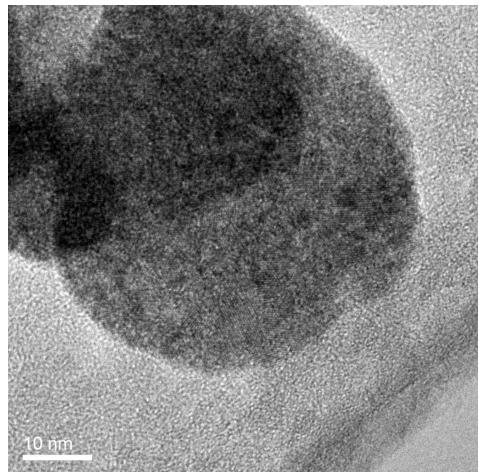
200 to 785 C

SF 4-9-8

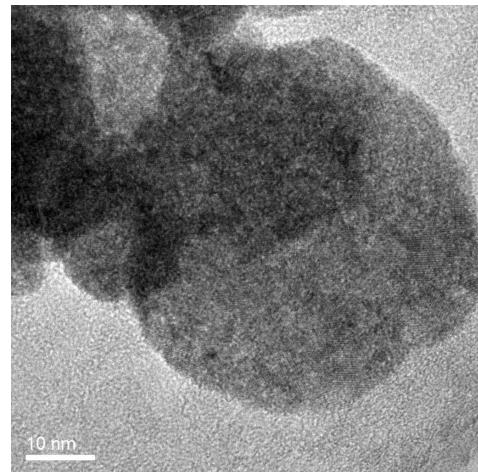


pH 5

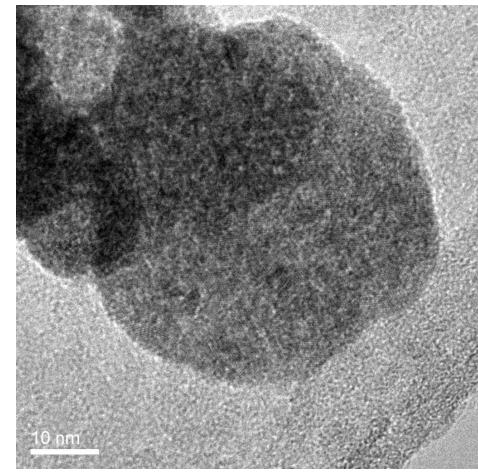
RT



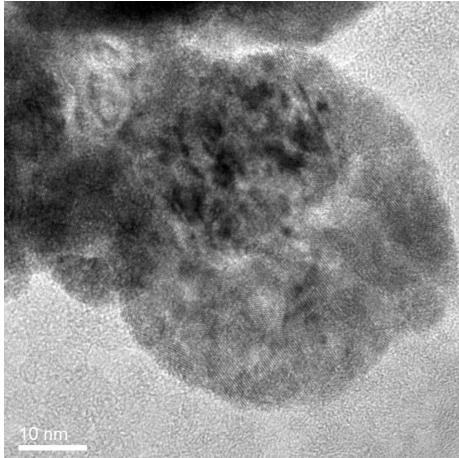
300 °C



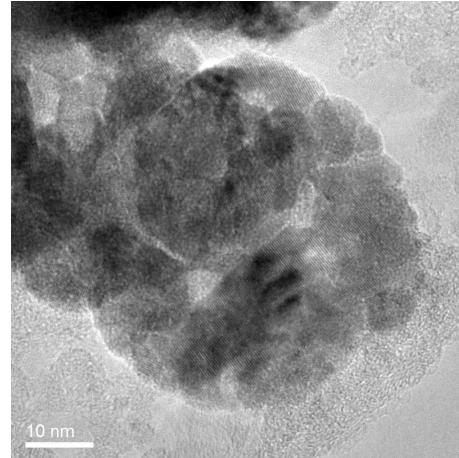
400 °C



600 °C



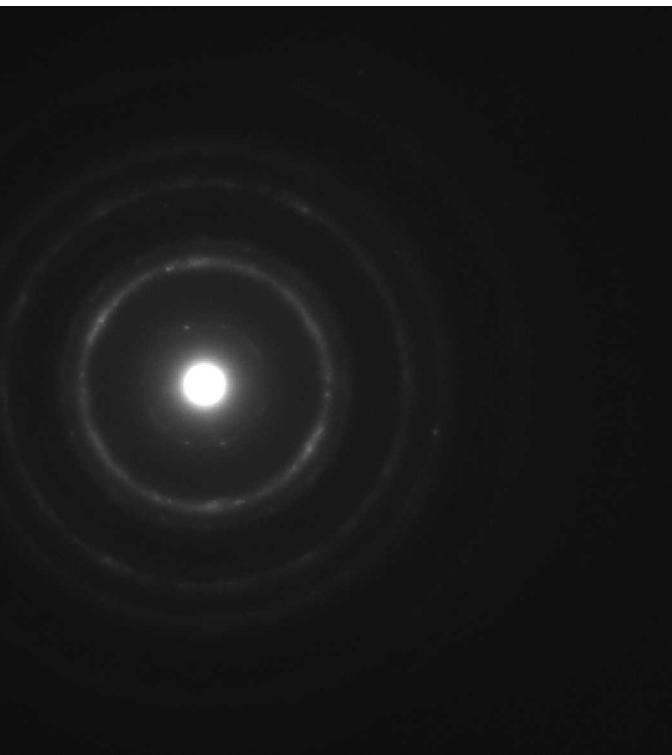
700 °C



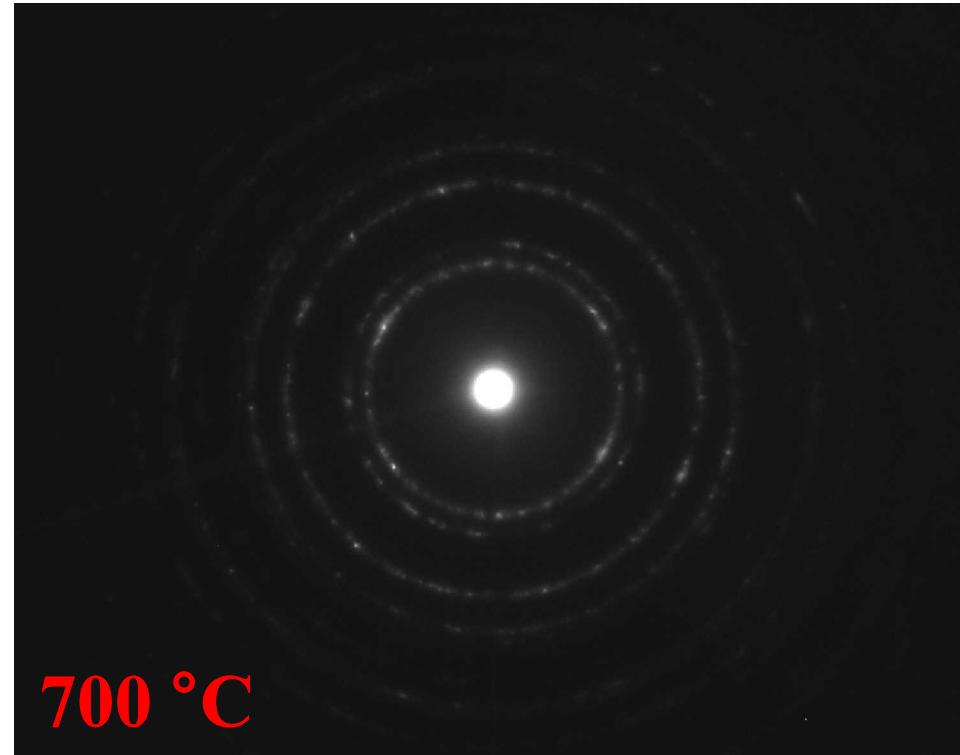


Electron diffraction, pH 5

Similar sintering (and not just condensation) occurs at pH 5



RT



700 °C



Summary and conclusions

Sandia (Albuquerque, NM, USA)

- UO_2 precipitation requires a balance between pH and reduction
 - Preferably avoid UO_2^{2+} precipitation, soluble U^{4+} , reoxidation
- UO_2 consolidates, UO_2^{2+} condenses upon heating
- Initial sintering processes occur well below bulk sintering temperatures (~ 1700 C)
- Product yield at low temperature can be optimized
- Initial low-temperature treatment may prove useful



Acknowledgements

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